

PATENT NUMBER

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U.S. **UTILITY** Patent Application

PD O.I.P.E. SCANNED <u>9W3</u> O.A. <u>AG</u>	PATENT DATE:
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APPLICATION NO. 09/532022	CONT/PRIOR F	CLASS <del>400</del> 355	SUBCLASS <del>1756</del> 30	ART UNIT <del>1756</del> 2851	EXAMINER H. Nguyen
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Yuji Sudoh  
Akiyoshi Suzuki

Exposure apparatus and a device manufacturing method which keep temperature of a diaphragm of a projection optical system substantially constant.

PTO-2040  
12/89☐ Continued on Issue Slip Inside File Jacket

**NOTICE OF ALLOWANCE MAILED**

ISSUE FEE	
Amount Due	Date Paid

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